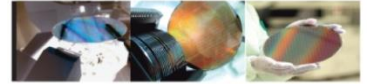


The Development and the commercialization of the Mask Aligner for wafer  
 Midas System will continue to grow along with the value creation for our customers.

<http://www.aligner.co.kr>

# MIDAS Exposure system MDA-400LJ



The MIDAS Exposure system is good for research and variable process of all applications. It represents next generation of full-field lithography systems.



ITEM	SPECIFICATIONS
Substrate Size	6" diameter
Light source	UV LED(365nm)
Uniform Beam Size	160mm
365nm Beam Intensity	$\leq 20\text{mW}/\text{cm}^2$
Beam Uniformity	$\leq 3\%(6'')$



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